and a vacuum loader side, and having a gate valve for said atmospheric loader side and another gate valve for said vacuum loader side,

wherein said vacuum loader has

(1) a transfer chamber connected to the lock chamber via the another gate valve, the method comprising the steps of:

transferring substrates, to be processed, from said atmospheric loader, exposed to the air, to said lock chamber;

after transferring substractes to the lock chamber, providing a vacuum in said lock chamber;

after providing a vacuum in said lock chamber, transferring substrates to be processed, from said lock chamber to said transfer chamber;

thereafter, transferring processed substrates from said transfer chamber to said lock chamber; and

transferring processed substrates from said lock chamber to said atmospheric loader from which the substrates had been transferred to the lock chamber.

wherein said gate valve and said another gate valve are opened and closed every carrying-in of a substrate, to be processed, to the lock chamber, and every carrying-out a processed substrate from the lock chamber.

- 2. (Amended) A method of transferring at least one wafer in a vacuum processing apparatus, comprising the steps of:
- (i) placing a cassette containing at least one wafer to be processed, at a cassette table, exposed to the air;





(ii) loading said at least one wafer sequentially in order from said cassette, by means of a first conveyor, to a load lock chamber, in which one wafer is to be disposed, and therefrom, by means of a second conveyor, to a transfer chamber under vacuum; and

(iii) after processing the wafers, unloading processed wafers from a plurality of vacuum processing chambers into said cassette at said cassette table, from which the wafers had been loaded, by means of the second conveyor in said transfer chamber under vacuum, an unload lock chamber, in which one wafer is to be disposed, and said first conveyor.

3. (Twice Amended) A method of transferring cassettes in operating a vacuum processing apparatus having plural vacuum processing chambers, the vacuum processing apparatus including:

an atmospheric loader exposed to the air;

a vacuum loader; and/

a lock chamber for connecting said atmospheric loader and said vacuum loader, said lock chamber having opening and closing devices for carrying-in wafers to be processed in the vacuum processing chambers into the lock chamber and for carrying-out processed wafers from the lock chamber, wherein

said atmospheric loader includes a cassette mount unit located in front of said lock chamber, and

said cassette mount unit has a cassette positioning plane in which all cassettes, containing samples to be

processed and exposed to the air, are positioned in front of a front wall of said lock chamber,

the method comprising a step of:

placing said cassette on and removing said cassette from said cassette mount unit which is in front of said lock chamber while maintaining a surface of the samples substantially horizontal.

wherein the opening and closing devices of the lock chamber are opened and closed every carrying-in of a wafer, to be processed, to the lock chamber, and every carrying-out of a processed wafer from the lock chamber.

9. (Amended) A method of operation a vacuum processing apparatus, the vacuum processing apparatus including:

an atmospheric loader, exposed to the air;

a vacuum loader; and

a lock chamber for connecting said atmospheric loader and said vacuum loader, said lock chamber having opening and closing devices for carrying-in samples, to be processed, into the lock chamber and for carrying-out processed samples from the lock chamber, wherein

said atmospheric loader includes a cassette mount unit located outside of said lock chamber, and

said cassette mount unit has a cassette positioning plane in which all cassettes, containing samples to be processed, exposed to the air, are positioned in front of a front wall of said lock chamber,

wherein the method comprises the steps of:

\$

carrying in a sample, disposed under atmospheric pressure, from a cassette, exposed to the air, in said cassette positioning plane, positioned in front of the front wall of said lock chamber, into at least one of a plurality of vacuum processing chambers of said vacuum processing apparatus, using said lock chamber;

ZD)

processing said sample in said at least one vacuum processing chamber; and

carrying out said sample, processed in said at least one vacuum processing chamber, into said atmospheric pressure, using said lock chamber,

wherein the opening and closing devices of the lock chamber are opened and closed every carrying-in of the sample, to be processed, to the lock chamber, and every carrying-out of the processed sample from the lock chamber.

11. (Amended) A method of operating a vacuum processing apparatus, the vacuum processing apparatus including:

an atmospheric loader, exposed to the air;

a vacuum loader; and

a lock chamber for connecting said atmospheric loader and said vacuum loader, said lock chamber having opening and closing devices for carrying-in samples, to be processed, into the lock chamber and for carrying-out processed samples from the lock chamber, wherein

said atmospheric loader includes a cassette mount unit located outside of said lock chamber, and

said cassette mount unit has a cassette positioning

plane in which all cassettes, containing samples to be processed, exposed to the air, are positioned in front of a front wall of said lock chamber,

processing said sample/in said at least one vacuum processing chamber; and

carrying out said sample, processed in said at least one vacuum processing chamber, into said atmosphere different from the atmosphere in said at least one vacuum processing chamber, using said lock/chamber,

wherein the opening and closing devices of the lock chamber are opened and closed every carrying-in of a sample, to be processed, to the lock chamber, and every carrying-out of a processed sample from the lock chamber.

13. (Twice Amended) A method of treating a sample in plural vacuum processing chambers comprising the steps of:

placing a cassette, containing the sample, at a position in front of a front wall of a lock chamber, on a cassette table, the cassette being exposed to the air, said lock chamber having opening and closing devices for carrying-in samples, to be processed, into the lock chamber and for

carrying-out processed samples from the lock chamber;

carrying in the sample into a vacuum processing chamber, of the plural vacuum processing chambers, using the lock chamber;

processing said sample in said vacuum processing chamber;

carrying out said sample, processed in said vacuum processing chamber to said cassette, using said lock chamber; and

removing said cassette from the cassette table,

wherein the opening and closing devices of the lock

chamber are opened and closed every carrying-in of a sample,

to be processed, to the lock chamber, and every carrying-out

of a processed sample from the lock chamber.

15. (Twice Amended) A method of treating a sample in plural vacuum processing chambers, comprising the steps of:

placing a cassette, containing the sample, on a cassette table, the cassette being exposed to the air;

carrying in the sample into a vacuum processing chamber, of the plural vacuum processing chambers, using a lock chamber, in which one sample is to be disposed;

processing said sample in said vacuum processing chamber;

carrying out said sample, processed in said vacuum processing chamber, to said cassette which had contained the sample prior to carrying the sample into the vacuum processing chamber, using said lock chamber, in which one sample is to be

ľ

disposed; and

removing said cassette from the cassette table.

16. (Amended) A method of treating a sample, comprising the steps of:

placing a cassette, containing the sample, at a position in a single row in front of a front wall of a lock chamber, on a cassette table, disposed under a cassette transferring atmospheric pressure, said lock chamber having opening and closing devices for carrying-in samples, to be processed, into the lock chamber and for carrying-out processed samples from the lock chamber;

carrying in the sample into a vacuum processing chamber, using the lock chamber;

processing said sample in said vacuum processing chamber; and

carrying out said sample, processed in said vacuum processing chamber, using said lock chamber.

wherein the opening and closing devices of the lock chamber are opened and closed every carrying-in of a sample, to be processed, to the lock chamber, and every carrying-out of the processed sample from the lock chamber.

17. (Twice Amended) A method of treating a semiconductor wafer in plural vacuum processing chambers, comprising the steps of:

placing a wafer storing structure, containing the semiconductor wafer, at a position in front of a front wall of

a lock chamber, on a wafer storing structure table, the wafer storing structure being exposed to the air;

carrying in the semiconductor wafer into a vacuum processing chamber, of the plural vacuum processing chambers, using a lock chamber, in which one semiconductor wafer is to be disposed;

processing said semiconductor wafer in said vacuum processing chamber; and

carrying out said semiconductor wafer, processed in said vacuum processing chamber, to said wafer storing structure which had contained the semiconductor wafer prior to carrying the semiconductor wafer into the vacuum processing chamber, using said lock chamber, in which one semiconductor wafer is to be disposed.

19. (Twice Amended) A method of treating a semiconductor wafer in plural vacuum processing chambers, comprising the steps of:

placing a wafer storing structure, containing the semiconductor wafer, at a position in front of a front wall of a lock chamber, in which one semiconductor wafer is to be disposed, on a wafer storing structure table, disposed under a wafer storing structure transferring atmospheric pressure;

carrying in the semiconductor wafer into a vacuum processing chamber, of the plural vacuum processing chambers, using the lock chamber;

processing said semiconductor wafer in said vacuum

processing chamber; and

carrying out said semiconductor wafer, processed in said vacuum processing chamber, to said wafer storing structure which had contained the semiconductor wafer prior to carrying the semiconductor wafer into the vacuum processing chamber, using said lock chamber, in which one semiconductor wafer is to be disposed.

21. (Twice Amended) A method of treating a sample in plural vacuum processing chambers, comprising the steps of:

placing a cassette, containing the sample, at a position in front of a front wall of a lock chamber, <u>in which</u> one sample is to be disposed, on a cassette table, the cassette being exposed to the air;

carrying in the sample into a vacuum processing chamber, of the plural vacuum processing chambers, using the lock chamber, in which one sample is to be disposed, wherein the sample is carried directly from the cassette to the lock chamber;

processing said sample in said vacuum processing chamber; and

carrying out said sample, processed in said vacuum processing chamber, to said cassette which had contained the sample prior to carrying the sample into the vacuum processing chamber, using said lock chamber, in which one sample is to be disposed.

23. (Twice Amended) A method of treating a sample in plural vacuum processing chambers, comprising the steps of:

placing a cassette, containing the sample, at a position in front of a front wall of a lock chamber, in which one sample is to be disposed, on a cassette table, the cassette being exposed to the air;

carrying in the sample into a vacuum processing chamber, of the plural vacuum processing chambers, using the lock chamber, in which one sample is to be disposed, wherein the sample is carried directly from the cassette to the lock chamber, samples being transferred from the cassette to the lock chamber;

processing said sample in said vacuum processing chamber; and

carrying out said sample, processed in said vacuum processing chamber, to said cassette from which the sample had been carried into the vacuum processing chamber, using said lock chamber, in which one sample is to be disposed.

25. (Twice Amended) A method of treating a sample in plural vacuum processing chambers, comprising the steps of:

placing a cassette, containing the sample, at a position in a row in front of a front wall of a lock chamber, on a cassette table, disposed under a cassette transferring atmospheric pressure, said lock chamber having opening and closing devices for carrying-in samples, to be processed, into the lock chamber and for carrying-out processed samples from the lock chamber;

carrying in the sample into a vacuum processing chamber, of the plural vacuum processing chambers, using the lock chamber, whereby the sample is carried into the lock chamber from the cassette;

processing said sample in said vacuum processing chamber; and

carrying out said sample, processed in said vacuum processing chamber, using said lock chamber, whereby the sample is carried out from the lock chamber to the cassette,

wherein the sample is carried from the cassette to the lock chamber in a direction opposite to the direction in which the sample is carried out from the lock chamber to the cassette, and

wherein the opening and closing devices of the lock chamber are opened and closed every carrying-in of the sample, to be processed, to the lock chamber, and every carrying-out of the processed sample from the lock chamber.

26. (Twice Amended) A method of treating a sample in plural vacuum processing chambers, comprising the steps of:

placing a cassette, containing the sample, at a position in a row in front of load and unload lock chambers, the load and unload lock chambers being separate chambers, the cassette being placed on a cassette table disposed under a cassette transferring atmospheric pressure, each of the load and unload lock chambers having opening and closing devices for carrying-in a sample to be processed in a vacuum processing chamber to the load lock chamber and for carrying-